

Substitute for form 1449A/PTO & 1449B/PTO		Complete if Known	
FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/764,407
		Filing Date	January 23, 2004
		First Named Inventor	Shenggao Liu et al.
		Examiner Name	
Sheet 1 of 1	3	Attorney Docket Number	005950-844

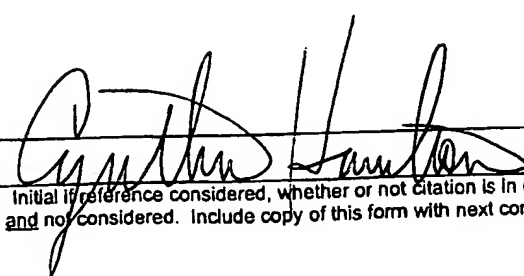
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Examiner Signature	Date Considered	9-8-05
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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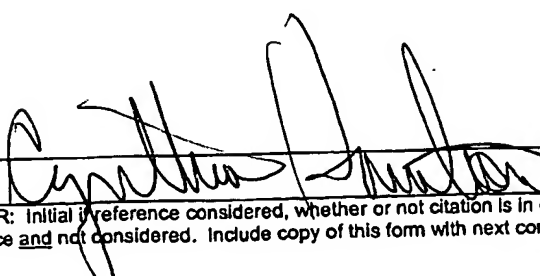
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					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited In Spec	
CH CH CH	WO 92/13909		PCT	08/20/92								
	WO 02/058139		PCT	07/25/02								
	WO 02/088077		PCT	11/07/02								

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
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9H	SHIDA, Naomi, "Advanced Materials for 193-nm Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp. 601-606
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